

UNITED STATES DEPARTMENT OF COMMERCE **Patent and Trademark Office**

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APPLICATION NO. FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO
	, · · .	EXAMINER ART UNIT PAPER NUMBER
		DATE MAILED:

Please find below and/or attached an Office communication concerning this application or proceeding.

Commissioner of Patents and Trademarks

	Application No.	Applicant(s)
Office Action Summary	09/433,062	SKUPIEN, THOMAS A.
	Examiner	Art Unit
	Sikha Roy	2879
The MAILING DATE of this communication a	appears on the cover sheet w	ith the correspondence address
A SHORTENED STATUTORY PERIOD FOR REF THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailling date of this communication. - If the period for reply specified above is less than thirty (30) days, a new order of the period for reply is specified above, the maximum statutory period Failure to reply within the set or extended period for reply will, by state than three months after the mail earned patent term adjustment. See 37 CFR 1.704(b).	N. 1.136(a). In no event, however, may a eply within the statutory minimum of thin od will apply and will expire SIX (6) MON	reply be timely filed ty (30) days will be considered timely. VTHS from the mailing date of this communication.
Status		
1)[:] Responsive to communication(s) filed on <u>03</u>		
	This action is non-final.	
3) Since this application is in condition for allow closed in accordance with the practice under the condition of the condition of the condition is in condition for allow closed in accordance with the practice under the condition of the condition of the condition is in condition for allow closed in accordance with the practice under the condition of the conditi	wance except for formal mai	tters, prosecution as to the merits is
Disposition of Claims	or Expante Quayle, 1955 C.I	J. 11, 453 O.G. 213,
4) Claim(s) is/are pending in the applica	tion	
4a) Of the above claim(s) is/are withdra		
5) Claim(s) is/are allowed.	ann nom consideration.	
6) Claim(s) <u>1-6</u> is/are rejected.		
7) Claim(s) is/are objected to.		
8) Claim(s) are subject to restriction and/	or election requirement	
Application Papers	a second requirement.	
9)☐ The specification is objected to by the Examine	er.	
10) The drawing(s) filed on is/are: a) acce	epted or b) objected to by th	a Evaminor
Applicant may not request that any objection to the	ne drawing(s) be held in abeyar	309 Soo 27 CED 4 05/->
11) The proposed drawing correction filed on	_ is: a) ☐ approved b) ☐ dis	Sapproved by the Examiner
if approved, corrected drawings are required in re	ply to this Office action.	The Examiner.
12) ☐ The oath or declaration is objected to by the Ex	kaminer.	
riority under 35 U.S.C. §§ 119 and 120		
\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\	. ,	. 10(a) (a) or (i).
a) ☐ All b) ☐ Some * c) ☐ None of:		
1. Certified copies of the priority document	s have been received.	
2. Certified copies of the priority document 3. Copies of the certified copies of the priority	s have been received in App	olication No
Copies of the certified copies of the prior application from the International Bu See the attached detailed Office action for a list		
14) Acknowledgment is made of a claim for domestic	c priority under 35 U.S.C. &	119(e) (to a provisional applications)
a) \(\) The translation of the foreign language pro 15) \(\) Acknowledgment is made of a claim for domesti	visional application has been	un ropoium d
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 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449) Paper No(s) 2 	4) Interview Sul 5) Notice of Info 6) Other:	mmary (PTO-413) Paper No(s)
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DETAILED ACTION

Drawings

The drawings filed on the application are acceptable subject to corrections of the informalities indicated on the attached "Notice of Draftperson's Patent Drawing Review", PTO-948.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1- 6 are rejected under 35 U.S.C. 103(a) as being unpatentable over U.

S. Patent 5,077,498 to Odenthal in view of U. S. Patent 5,204,585 to Chen and further in view of U. S. Patent 5,734,235 to Noguchi.

Odenthal discloses (Fig. 1 column 4 lines 32-38,55-59,column 5 lines3-20) a cathode ray tube comprising an electron gun including cathode producing a beam of

focus electrode (focus ring) 52 positioned between second accelerating electrodes 54 and final accelerating electrode 56. The einzel focus lens 16 forms an electron beam with low spherical aberration. The focus electrode 52 receives a potential via one of the base pins 51. The outer electrodes 54 and 56 receive a voltage between 12 and 24 kilovolts.

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Odenthal does not disclose final accelerating electrode being conductive coating on the neck and the second accelerating electrode being connected to an external potential via the high voltage stem pin.

Chen in analogous art of electron beam deflection lens for CRT discloses (column 9 lines 10-25 Fig.5) the outer electrode (G6) disposed in the form of a conductive coating deposited on the inner surface of the glass envelope and electrically coupled to the anode button for receiving the anode voltage V_A. It is further noted (column 9 lines60-66) that the main focus lens of the electron gun has a larger diameter and hence reduces electron beam spherical aberration and improves the electron beam spot on the CRT display screen.

Therefore it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify the final accelerating electrode 56 of the einzel focus lens of Odenthal to an internal conductive coating connected to anode potential as suggested by Chen for increasing the diameter of the main focusing lens and hence reducing electron beam spherical aberration.

Noguchi in relevant art of electron gun with reduced astigmatism discloses voltages supplied from stem pins provided in the stem. Noguchi teaches the final accelerating voltage supplied from the anode button and the focus voltage V_f in a range of 3 to 12 kv supplied via pin 101. Accordingly the number of the kinds of high focus voltages to be supplied via stem pins is reduced to only one, so that the electron gun for use in a

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cathode ray tube eliminates the need for any special socket for supplying a voltage thereto (column 6 lines33-35).

Therefore it would have been obvious to one of ordinary skill in the art at the time the invention was made to use the isolated high voltage stem pin for supplying high voltage of 12 kv to the second accelerating electrode 54 and other pins for supplying low voltages to other electrodes of Odenthal as taught by Noguchi for eliminating the need for any special type of socket.

Referring to claims 2 and 4, Odenthal in view of Chen discloses the potential supplied to the second accelerating and final accelerating electrodes being same and equal to the anode potential. Hence the external potential supplied by the high voltage stem pin to the second accelerating electrode is the anode potential.

Referring to claims 3,5 and 6 Odenthal discloses (column 10 lines 7-10) the high voltage potential applied to the outer electrodes has a magnitude of between 12 kv and 24 kv.

Conclusion

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applicant's disclosure. The following references are cited to further show the state of the art with respect to electron gun assembly with improved focusing of electron beams.

- U. S. Patent No. 3,863,091 to Hurukawa et al.
- U. S. Patent No. 4,745,331 to Alig
- U. S. Patent No. 6,025,674 to Tojyou et al.

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Contact Information

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Sikha Roy whose telephone number is (703) 308-2826. The examiner can normally be reached on Monday-Friday 8:00 a.m. -4:30 p.m.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nimeshkumar D. Patel can be reached on (703) 305-4794. The fax phone number for the organization is (703) 308-7382.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

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Sikha Roy Patent Examiner Art Unit 2879

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